

This Page Is Inserted by IFW Operations
and is not a part of the Official Record

BEST AVAILABLE IMAGES

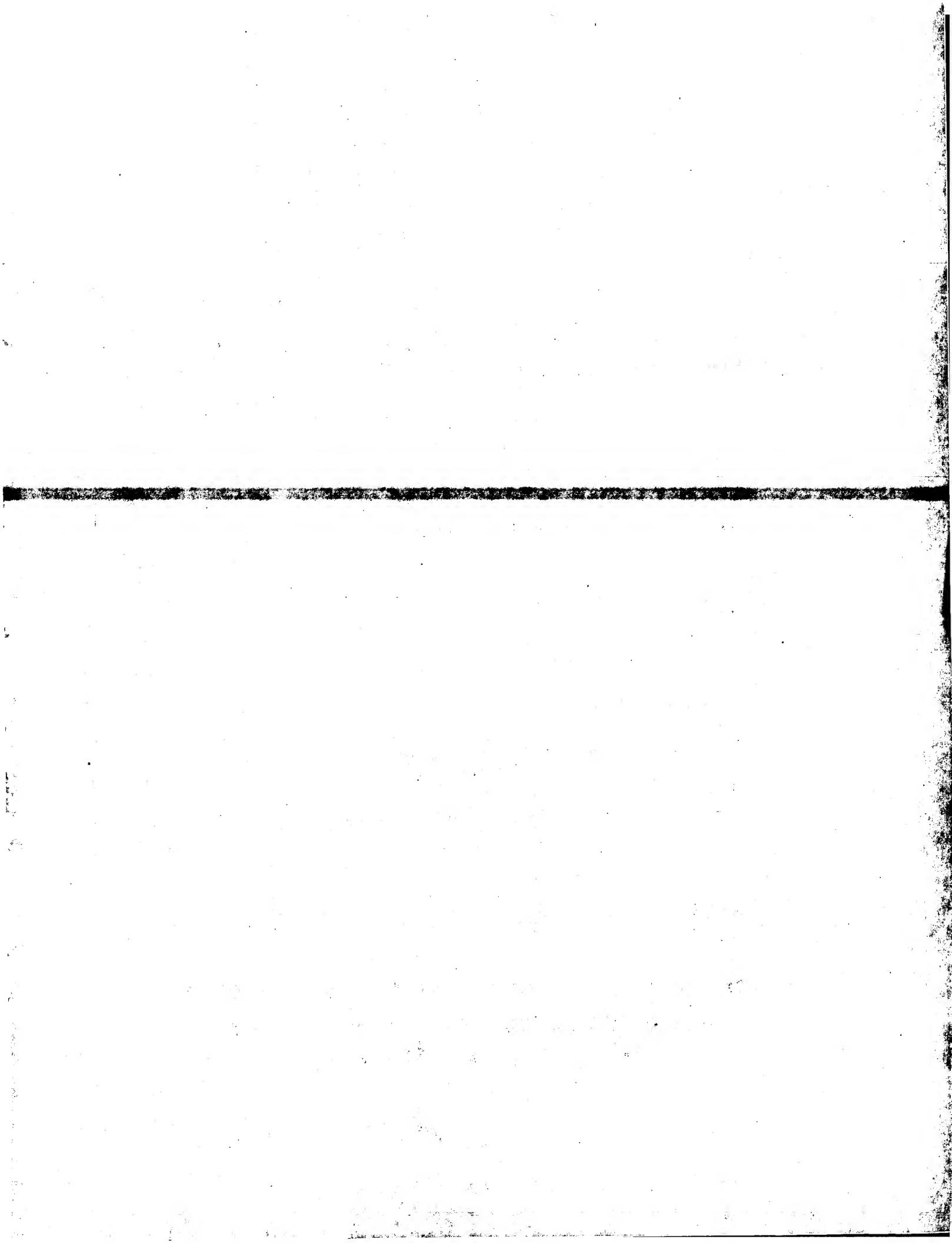
Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images may include (but are not limited to):

- BLACK BORDERS
- TEXT CUT OFF AT TOP, BOTTOM OR SIDES
- FADED TEXT
- ILLEGIBLE TEXT
- SKEWED/SLANTED IMAGES
- COLORED PHOTOS
- BLACK OR VERY BLACK AND WHITE DARK PHOTOS
- GRAY SCALE DOCUMENTS

IMAGES ARE BEST AVAILABLE COPY.

**As rescanning documents *will not* correct images,
please do not report the images to the
Image Problem Mailbox.**

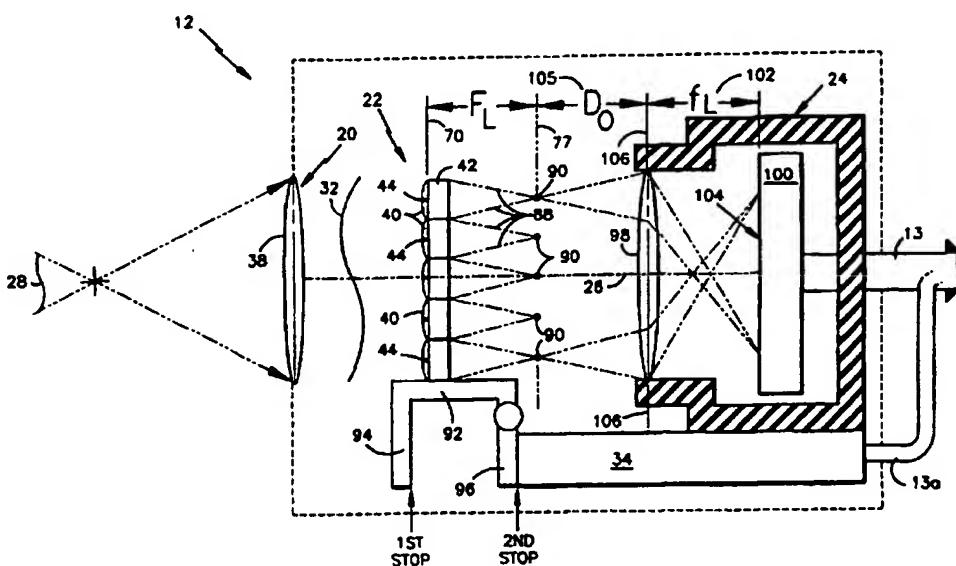




INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification ⁶ : G01J 9/00		A1	(11) International Publication Number: WO 97/21989 (43) International Publication Date: 19 June 1997 (19.06.97)
(21) International Application Number: PCT/US96/20388		(81) Designated States: JP, European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE).	
(22) International Filing Date: 13 December 1996 (13.12.96)		Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>	
(30) Priority Data: 572,907 15 December 1995 (15.12.95) US			
(71) Applicant: ADAPTIVE OPTICS ASSOCIATES, INC. [US/US]; 54 Cambridge Park Drive, Cambridge, MA 02140-2308 (US).			
(72) Inventor: SCHMUTZ, Lawrence, E.; 183 Lovell Road, Watertown, MA 02172 (US).			
(74) Agent: KELLY, Robert, H.; Intellectual Property Counsel, Hamilton Standard, One Hamilton Road, Windsor Locks, CT 06096-1010 (US).			

(54) Title: WAVEFRONT MEASURING SYSTEM WITH INTEGRAL GEOMETRIC REFERENCE (IGR)



(57) Abstract

A geometric sensor includes a Monolithic Lenslet Module (MLM) subaperture array (22) having a plurality of microlenses (40), each of which have an opaque center marking formed concentric with the microlens optical axis (44), at the location of the lens chief ray, to produce an integral geometric reference (IGR) spot pattern of the lens array which is used to correct for sensor errors to an accuracy comparable with that achieved with reference plane wave calibration.

FOR THE PURPOSES OF INFORMATION ONLY

Codes used to identify States party to the PCT on the front pages of pamphlets publishing international applications under the PCT.

AM	Armenia	GB	United Kingdom	MW	Malawi
AT	Austria	GE	Georgia	MX	Mexico
AU	Australia	GN	Guinea	NE	Niger
BB	Barbados	GR	Greece	NL	Netherlands
BE	Belgium	HU	Hungary	NO	Norway
BF	Burkina Faso	IE	Ireland	NZ	New Zealand
BG	Bulgaria	IT	Italy	PL	Poland
BJ	Benin	JP	Japan	PT	Portugal
BR	Brazil	KE	Kenya	RO	Romania
BY	Belarus	KG	Kyrgyzstan	RU	Russian Federation
CA	Canada	KP	Democratic People's Republic of Korea	SD	Sudan
CF	Central African Republic	KR	Republic of Korea	SE	Sweden
CG	Congo	KZ	Kazakhstan	SG	Singapore
CH	Switzerland	LI	Liechtenstein	SI	Slovenia
CI	Côte d'Ivoire	LK	Sri Lanka	SK	Slovakia
CM	Cameroon	LR	Liberia	SN	Senegal
CN	China	LT	Lithuania	SZ	Swaziland
CS	Czechoslovakia	LU	Luxembourg	TD	Chad
CZ	Czech Republic	LV	Latvia	TG	Togo
DE	Germany	MC	Monaco	TJ	Tajikistan
DK	Denmark	MD	Republic of Moldova	TT	Trinidad and Tobago
EE	Estonia	MG	Madagascar	UA	Ukraine
ES	Spain	ML	Mali	UG	Uganda
FI	Finland	MN	Mongolia	US	United States of America
FR	France	MR	Mauritania	UZ	Uzbekistan
GA	Gabon			VN	Viet Nam

Description**WAVEFRONT MEASURING SYSTEM WITH
INTEGRAL GEOMETRIC REFERENCE (IGR)****Technical Field**

5 This invention relates to wavefront measuring systems, and more particularly to geometric type wavefront sensors.

Background Art

There are a number of known adaptive optics applications which require the measurement of wavefront distortion in light received from a viewed object. 10 These include optical correction systems in which the conjugate of the sensed distortion drives a deformable mirror in the received wavefront's optical path to provide real time image compensation, and measurement systems which provide non-real time measurement of the optical quality of a laser beam or a manufactured optical component. Each application measures the wavefront phase profile with a wavefront sensor. Two known types of sensor 15 configurations include the interferometric sensor, such as the Twyman-Green, Fizeau, and shearing interferometer sensors, and the geometric type, such as the Hartmann-Shack sensor.

20 In an interferometric sensor a wavefront is measured by coherently adding it to a mutually coherent plane wavefront and measuring the spatial distribution of the intensity variations in the resultant combined wavefront. For example, in a Twyman-Green sensor, a single plane coherent wavefront, prepared using a frequency stabilized laser and precision collimating optics, is split into two components using an optically flat 25 beam splitter. One component is directed onto an optical component under test, such as a flat mirror which is being tested after manufacture, and the reflected

wavefront is recombined with the remainder of the original wavefront using the same beam splitter that first divided it. The combined beams then impinge upon a flat diffusely scattering surface, such as a screen or diffuser, or onto a two-dimensional detector array, such as a charge coupled device (CCD), creating an interference pattern. Any aberrations in the mirror under test cause deviations in the interference pattern, which can be measured and mathematically analyzed to yield a quantitative description of the profile of the test mirror. The key to accuracy here is the generation of a truly plane, phase coherent plane wave with which the testing can be performed.

10 The interferometric sensor's complex structure limits their accurate use to environments which are relatively free of vibration, air motion, and sharp temperature variations. Without these control conditions the contrast in the interference fringes used in the technique is reduced; reducing the base accuracy of the sensor. Similarly, calibration of an interferometric sensor requires the use 15 of high quality, stable frequency, laser-generated plane wave, together with precisely made reference mirrors, collimating lenses and beam combiners. Their sensitivity and costly calibration optics principally limit the use of interferometric sensors to laboratory applications.

20 Alternatively, geometric sensors, such as that disclosed by Julius M. Feinleib in United States patent 4,141,652, are more rugged and provide measurement accuracies that compare favorably with interferometric sensors. The geometric sensor divides the full aperture input wavefront into plural subaperture images with an array of small diameter lenses. The subaperture images are focused as a two dimensional spot pattern onto a photodetector array 25 which provides the X-Y phase gradient of each spot image as a representation of the average tip/tilt of each subaperture segment. Each segment phase gradient is converted to a phase estimate by a microprocessor-based reconstruction algorithm and the sum of the phase estimates provides a reconstruction of the wavefront's full aperture phase profile. Measurement inaccuracies due to optical 30 distortion or misalignment of the sensor's optics are minimized by combining the received wavefront with an internal reference laser wavefront upstream of the

subaperture optics and measuring subaperture tilt/tip as the difference spot position between the two waves. Since the reference wave suffers no atmospheric distortion, any displacement of the reference wave's subaperture spot position from that of the subaperture's chief ray is attributable to sensor 5 distortion. The differential spot position between the two waves, therefore, provides an accurate measure of the received wavefront's distortion.

The geometric sensor is more tolerant of vibration and temperature conditions which, together with its simplicity, allows it to be used in a greater number of adaptive optic applications outside of the laboratory. However, prior 10 art geometric sensors also require a high quality calibration standard in the form of an accurate plane wave laser and collimating optics, as in the sensor configuration disclosed by Julius N. Feinleib and Lawrence E. Schmutz in statutory invention registration (SIR) H615 (see 35 U.S.C. 157) entitled: High Speed/Low Light Wavefront Sensor System (April 4, 1989).

15 Referring to Figure 1 of H615, as reproduced herein, the received wavefront (or target beam) 4 is combined with a reference light beam from reference laser 1 in beam combiner 5. The combined beams are presented alternately, through optical switching means, through foreoptics 6 to a subaperture lens array 7, which produces the subaperture spot pattern that is 20 intensified in image intensifier 8 and presented to a photodetector array 9. The phase gradient data from the detector is then reconstructed into the target beam phase profile by the system's signal processor 10.

The H615 subaperture lens array is a Monolithic Lenslet Module (MLM) of the type manufactured by Adaptive Optics Associates, Inc.(AOA), 25 Cambridge, Massachusetts. The MLM is a precision array of plural refractive microlenses formed in a monolithic optical substrate. The prior art Figure 2 herein is a reproduction of the H615 SIR Figure 2 which depicts, in simplified schematic form, the operation of MLM 7. As recited in H615, at column. 5, lines 7 et seq:

30 **In the diagram of FIG. 2, the incoming wavefront having a phase distribution $\phi(x,y)$ impinges on a two-dimensional array**

5

f lenses which is located at a pupil plane of the optical system. This lens array is referred to as a **Monolithic Lenslet Module**, or **MLM**. Each lens in the MLM intercepts a small segment, or subaperture, of the full system aperture. a 2D array of spots, each spot corresponding to one subaperture, is thereby formed behind the MLM at the lens focal length F. Each spot is an image of the source illumination or target.

10

For a perfectly flat, tilt-free plane wave ($\phi(x,y) = \text{constant}$), all spots will fall directly on the optical axis of their subapertures. For an aberrated wavefront, each spot is displaced from its nominal position by an amount $r(x,y)$, where r is given by: $r(x,y) = F g(x,y)$ and $g(x,y)$ is the gradient of the phase distribution: $g(x,y) = \nabla \phi(x,y)$.

15

The H615 sensor, requires use of a reference plane wave having $\phi(x,y) = \text{constant}$, which is provided by the laser source 1 and beam combiner optics 5 (Fig. 1) to establish a reference spot pattern whose spot locations are recorded by processor 10 and subtracted from the target beam spots to remove the sensor's optical and electronic systematic errors. However, the reference plane wave signal source and collimating optics must be of high quality, and add significantly to the sensor's cost.

20

There exists, therefore, a need for a lower cost, acceptable accuracy geometric wavefront sensor which does not require a plane wave reference to maintain its accuracy during ordinary operation.

Disclosure of Invention

25

One object of the present invention is to provide an improved geometric wavefront sensor having sensed accuracy equal to prior art geometric sensors but with a simpler configuration and lower cost.

30

According to the present invention, a geometric sensor includes a **Monolithic Lenslet Module (MLM)** which incorporates a reference spot pattern, or integral geometric reference, within the MLM array itself by providing each

5 microlens with a substantially opaque center portion; each opaque element, referred to as a reference fiducial point, is precisely positioned concentric with the lens optical axis, at the location of the lens chief ray, whereby the aggregate of the fiducial points produce an integral geometric reference spot pattern which is equivalent to the spot produced by an ideal plane wavefront signal.

In further accord with the present invention, the geometric sensor further comprises a combination lens and photodetector assembly which is alternately positioned at different locations along the beam path of the subaperture images, from the MLM pupil plane to the MLM focal plane, to allow the detector to 10 alternately record both the focused subaperture spot pattern of the focal plane and also the internal geometric reference spot pattern of fiducial points in the MLM pupil plane, thereby allowing for comparison of the two spot patterns to determine subaperture phase gradient.

15 The geometric sensor of the present invention provides an accurate internal calibration standard in the form of an internal geometric reference which may be incorporated within the sensor subaperture MLM array, thereby eliminating the cost and complexity associated with a reference wave calibration standard.

20 These and other objects, features, and advantages of the present invention will become more apparent in light of the following detailed description of a best mode embodiment thereof, as illustrated in the accompanying Drawing.

Brief Description of Drawings

25 Fig. 1, is a reproduction of the prior art Figure 1 of statutory invention registration (SIR) H615 entitled: High Speed/Low Light Wavefront Sensor System (April 4, 1989);

Fig. 2 is a reproduction of the prior art Figure 2 of SIR H615;

Fig. 3 is a system block diagram of a best mode embodiment of a wavefront sensor system according to the present invention;

Fig. 4 is a schematic block diagram illustrating one element of the sensor system of Figure 3;

Fig. 5 is a partial plan view of tooling used in the manufacture of a component of the embodiment of Fig. 4;

5 Fig. 6 is an illustration of the operation of the tooling of Fig. 5;

Fig. 7 is an illustration used in a description of the operation of the embodiment of Fig. 4;

Fig. 8 is another illustration used in conjunction with Fig. 7 in describing the operation of the embodiment of Fig. 4; and

10 Fig. 9, is a schematic block diagram illustrating an operating feature of the embodiment of Fig. 4.

Best Mode for Carrying out the Invention

Referring to Fig. 3, the wavefront sensor system 10 of the present invention includes a geometric sensor 12, connected through lines 13, 13a to a system signal processor 14. The signal processor, which may be a commercially available, DOS based PC with an INTEL® PENTIUM® microprocessor, includes a standard full keyset keyboard 16 and a display 18. The display is a standard SVGA monitor with a 256 color video driver.

In the best mode embodiment, the sensor 12 includes foreoptics 20, a Monolithic Lenslet Module subaperture lens array 22, and a camera 24; successively positioned along the sensor's optical axis 26. As in prior art geometric sensors, the foreoptics 20 relays the received wavefront 28 of an optic under test 30 as a smaller radial scale, full aperture image 32 to the subaperture MLM array 22. Similarly, the MLM array 22 divides the image 32 into plural subaperture images which are presented to the camera 24. As described in detail hereinafter, the camera 24 is mounted on a movable platform 34 which moves in reciprocal fashion along a path 36; substantially parallel to the sensor's optical axis 26. The system signal processor 14 controls the position of the platform 34 on the path 36 through lines 13.

30 Referring now to Fig. 4, in a schematic illustration of the sensor 12, the

foreoptics 20 comprises a standard doublet lens 38 for collimating the received wavefront 28 of the optic under test into the scaled full aperture image 32.

Typically the lens 38 would have what is known to those skilled in the art as "best form" for laser collimation.

5 Alternatively, as also understood by those skilled in the art, the incorporation of foreoptics 20 in the sensor configuration is optional. They may be eliminated in applications in which the sensor's host measurement system itself provides an acceptable, scaled full aperture image directly to the MLM 22.

10 The MLM 22 array is similar in type to prior art MLMs manufactured by Adaptive Optics Associates, Inc. (AOA) in that it comprises a precision array of plural refractive microlenses 40, formed contiguously on a monolithic optical substrate 42. The microlenses 40 are typically compression molded of polymethylmethacrylate (PMMA) plastic. They are positioned in the substrate 42 with full edge-to-edge lenslet contact to maximize the MLM density of lens area 15 to total surface area (referred to as "fill factor"). The fill factor determines how much of the scaled full aperture image 32 is captured in subaperture images, and the commercial MLMs manufactured by AOA have fill factors exceeding 98 percent.

20 The MLM 22 of the present sensor is novel, however, in that it produces a reference spot pattern, or integral geometric reference, within the lens array itself. The integral geometric reference (or IGR) is achieved by incorporating a substantially opaque element 44 at the center of each microlens of the MLM. The opaque element 44, referred to as a reference fiducial point, or "fiducial" is accurately positioned at the optical axis of each microlens, at the location of lens 25 chief ray. The fiducial surface area is relative to the microlens clear aperture diameter, which varies with the particular sensor application. It must be large enough to provide a suitable intensity IGR spot image to the detector but small enough to have minimal affect on the lens subaperture image. Depending on the particular sensor application, the fiducial area may range from 5% to 20% of the 30 microlens surface area.

The AOA fabrication techniques for the MLM maintains an accurate, constant relationship between the position of the fiducial element 44 and the microlens true optical axis 26 (chief ray location). This is achieved with extremely high repeatability using a step-and-repeat method for creating an 5 MLM tooling master which incorporates the fiducial elements in the lenslet mold. Fig. 5 illustrates a portion of the manufacturing tooling used to create the internal geometric reference MLM.

Referring to Fig. 5, a tool stylus 48 includes a shaft 50 having a conical seat 51 at one end of the shaft. An embossing die 52 is mounted in the seat 51 and secured with a known type cement 53, such as cyanoacrylate. The die 52 may be a highly polished, spherical ball having a radius R 54, which establishes the curvature radius of the MLM lenslets, and incorporating the fiducial indent 56 in the lenslet surface profile 58. The indent 56 may be formed in the surface of the die 52 by a number of alternative methods, including mechanical or laser drilling, or spark cutting. The exact method used depends on the embossing die 10 material.

Fig. 6 is a figurative illustration of the tool 48 being used to emboss the microlens surface 58 of the die 52 into an MLM tooling master 60. As known, the MLMs are formed by using a tooling master die to compression mold optical 20 substrate materials, such as optical plastic, to form the microlens array. The stylus is installed in a step-and-repeat engine (not shown) which reciprocates (arrow 61) the shaft 50 to allow the die 52 to repeatedly impact succeeding points on the surface 62 of the tooling master mold 60 as it moves in a direction 64 transverse to the die 52. The master comprises a malleable material. Each die 25 impact embosses the tooling surface 62 to replicate the die radius 54 and fiducial detent 56 (Fig. 5) in the surface 62. The step and repeat process permits the formation of identical, successively arrayed, lenslet impressions 65, each with a radius 66 and fiducial indent 68 identical to those of the die 52. It should be noted that although the lenslets may not be located accurately in the tooling due 30 to errors in positioning during the step-and-repeat process, the spatial

relationship between the fiducial and the optical axes of the lenslets is perfectly preserved, because this relationship is built into the stylus.

Referring now to Fig. 7, in a sectioned, schematic view of the MLM 22, the array of microlenses 40 are positioned in the pupil plane 70 of the MLM, 5 together with the fiducials 44 which are positioned concentric to the optical axes 72 of the lenses. Upon incidence of a tilt free plane wave 74 ($\phi(x,y) = \text{constant}$) the MLM array focuses the plane wave subaperture images to spot images 76 in the MLM focal plane 77. The plane wave spot images coincide with the lenslet optical axes 72 (i.e. each lenslet's chief ray) such that the pattern of the plane 10 wave's spot images exactly coincides with the pattern of the internal geometric reference provided by the fiducials 44.

Alternatively, Fig. 8 illustrates a plane wave 80 which is incident at an angle ϕ . The resulting pattern of subaperture spots 84 in the focal plane 77 has the same pattern as that of the fiducial spot images 86, but the two patterns are 15 displaced by a constant distance ϕF , where ϕ is the angle of incidence and F is the MLM focal length. The image of the fiducial spots is therefore equivalent to the external reference wave, to within a correction for full aperture tilt (ϕF).

Referring back to Fig. 4, the MLM 22 focuses the ray bundles 88 of each subaperture image to a pattern of spots 90 in the MLM focal plane 77. Since 20 fundamental accuracy of the geometric sensor depends on the accuracy to which the quantities x_l and y_l (the locations of the subaperture lenslet centers), Δx and Δy (the displacements of the subaperture image spots from the lenslet optical axis), and F (the focal length or pupil-to-focal plane distance) can be maintained, the MLM 22 is mounted in a stable mechanical structure 92 which includes two 25 mechanical stops 96, 94, which are spaced apart at a distance equal to the MLM pupil plane to focal plane distance.

The camera 124 includes a relay lens 98 and a photodetector array 100. The camera is fixedly mounted to the camera platform 34. The platform 34 is a single-axis movable stage, such as a dovetail, which permits only uniaxial 30 motion, or a crossed roller bearing stage, which like a dovetail permits only uniaxial motion but with a low friction bearing configuration. This permits the

camera 124 to focus in several different image planes along the subaperture beam path, in a manner similar to the geometric measurement system disclosed in a published article entitled: *Applying Hartmann Wavefront Sensing Technology to Precision Optical Testing of the Hubble Space Telescope Correctors*, by L. 5 Bruno, A. Wirth, and A. J. Jankevics, PROCEEDINGS OF THE SPIE, Vol. 1920, pages 328-336 San Diego, 1993.

The camera may be a standard RS-170 type monochrome video camera, such as those manufactured by PULNIX, Inc. or COHU, Inc., however, such other known model cameras may be used as may be deemed suitable for use by 10 those skilled in the art. As described hereinafter, in the best mode embodiment the camera is positioned at fixed stops along the subaperture beam path. It may be moved or retracted by any suitable means, including manual positioning by an operator if permitted by the time constraints of the particular application. Alternatively, the pre-stops may be eliminated and the platform can be motorized 15 with a stepper motor drive. The particular means of actuation is necessarily determined on an application basis.

The lens 98 is fixed within the camera at its focal length (f_L) 102 from the detector 100 receiving surface 104. The camera 124 is also fixed in position on the platform 34 so as to position the relay lens 98 at its object distance (D_o) 105 from the MLM focal plane 77 when the platform 34 is positioned against the engaged second stop 96.

With the second stop engaged, the pupil plane 106 of the lens 98 is positioned at its object distance D_o from the MLM focal plane 77 such that the focal plane array of spots is imaged on the detector surface 104. In this position 25 the sensor 12 is operating in its normal measurement mode. With the second stop 96 disengaged, platform 34 is moved forward toward the MLM 22 until the platform comes to rest against the first stop 94 as shown in Figure 9. This positions the entrance pupil 106 of the camera at a distance D_o from the pupil plane 70 of the MLM array 22, such that the array of lenslets and their fiducial 30 elements are imaged onto the detector array 100. In this position the sensor is operating in its calibration mode.

In the calibration mode the array of fiducial marks appears at the detector surface 104 as an array of spots exactly co-aligned with the centers of each lens.

The centroid of each spot is then used to develop a look-up table which is used in precisely the same way as the table generated using a laser reference system.

5 By incorporating the fiducials in the substance of the lenses themselves, the resulting calibration approach is far less expensive and far more stable than is the use of the laser plane wave generator.

Such a system also permits the lens array, mount and mechanical stop assembly to be configured as a replaceable module in the sensor system, so that 10 arrays having different numbers and patterns of lenses, as well as different focal lengths can be inserted to give the sensor different properties. Calibration of the sensor would be ensured by accurate fabrication of the fiducials and the locations of the mechanical stops on each new assembly. Other information (such as lenslet pattern and focal length) which should be communicated to the wavefront 15 sensor processor to configure the software to accommodate the replacement assembly can easily be incorporated in a digital data file created at the time of lens assembly manufacture, and included with the assembly on some transportable medium such as a floppy disk.

The accuracy with which the integral geometric references (IGR) can be 20 used depends on the systematic error sources present in the sensor design. The major sources are:

- 1) Aberrations in the input optics (or foreoptics) coupling the input beam to the MLM.
- 2) Variations in the locations of the individual lenslets from a perfect regular array.
- 3) Time-varying changes in the MLM dimensions and focal lengths due to environment (temperature, vibration, etc.).
- 4) Variations in the image transfer optics between the MLM and the camera focal plane,
- 30 5) Detector plane non-uniformity and time variance.

6) Electronic drifts, etc. in signal acquisition paths (especially in multi-tab, parallel channel detectors).

Of the listed errors, all but the Source 1 errors associated with aberrations in the foreoptics may be corrected with an IGR system. These 5 Source 1 errors must either be designed out of the system or calibrated by other means. This is very practicable in many applications.

The Source 2 error is completely corrected by the IGR which maintains an accurate, constant relationship between the fiducial position and the lenslet 10 true optical axis (chief ray location), since the position of the lenslet is given by the position of the fiducial to within a constant term which is equivalent to full aperture tilt.

The Source 3 error is very small because of the stability inherent in the MLM fabrication approach described. In this case, the IGR model sensor corrects for lateral dimensional variations, but not focal length changes.

15 The IGR technique corrects for the most important error terms involving the listed Sources 5 and 6. It does this as accurately as the corrections performed using the prior art reference laser plane wave methods. Similarly the errors of Source 4 is also corrected, with the proviso that care must be taken to design the relay optics such that the magnification change between the MLM pupil plane 70 and its focal plane 77 is small, or at least well-characterized.

20 The IGR geometric sensor of the present invention provides a measurement accuracy that favorably compares with that provided by prior art 25 geometric sensors, but at a substantially reduced sensor cost due to elimination of the reference wave source and calibration optics. Similarly, the simplicity of the IGR sensor configuration permits its greater tolerance to environmental field conditions, and allows the sensor to be used in a greater number of practical applications.

Although the invention has been shown and described with respect to a best mode embodiment thereof, it should be understood by those skilled in the art that various changes, omissions, and additions may be made to the form and detail of the disclosed embodiment without departing from the spirit and scope of the invention as recited in the following claims.

5

Claims

1. A geometric wavefront sensor, for use in a system of the type having a signal processor for determining a phase gradient of a received full aperture wavefront as the aggregate of the difference coordinate positions between two dimensional spot images of the received full aperture wavefront and a reference wavefront in each of a plurality of subapertures, the sensor comprising:

5 a monolithic lens module (MLM), having a plurality of subaperture lenses arrayed in a MLM pupil plane for dividing the received full aperture wavefront into plural subaperture images and for focusing each as a two dimensional spot image in a MLM focal plane located on subaperture beam path at a MLM focal length from said MLM pupil plane; and

10 camera means, for providing an electrical signal equivalent of each of said subaperture spot images to the signal processor;

as characterized by:

15 each said subaperture lens having an integral geometric reference (IGR) disposed thereon in the form of a substantially opaque center portion concentric with a lens optical axis, at the location of the lens chief ray, each said IGR identifying its associated subaperture lens with an IGR spot image equivalent of a reference plane wave in said MLM pupil plane; and

20 said camera means providing electrical signal equivalents of said subaperture spot and, alternately, each of said IGR spot images to the signal processor which determines therefrom the phase gradient of the received full aperture wavefront as the aggregate of the difference coordinate positions in the subaperture spot image and the IGR spot image from each said subaperture lens.

2. The sensor of claim 1, wherein said camera means comprises:

relay lens, having an optical axis, and having a lens object distance and a lens focal length;

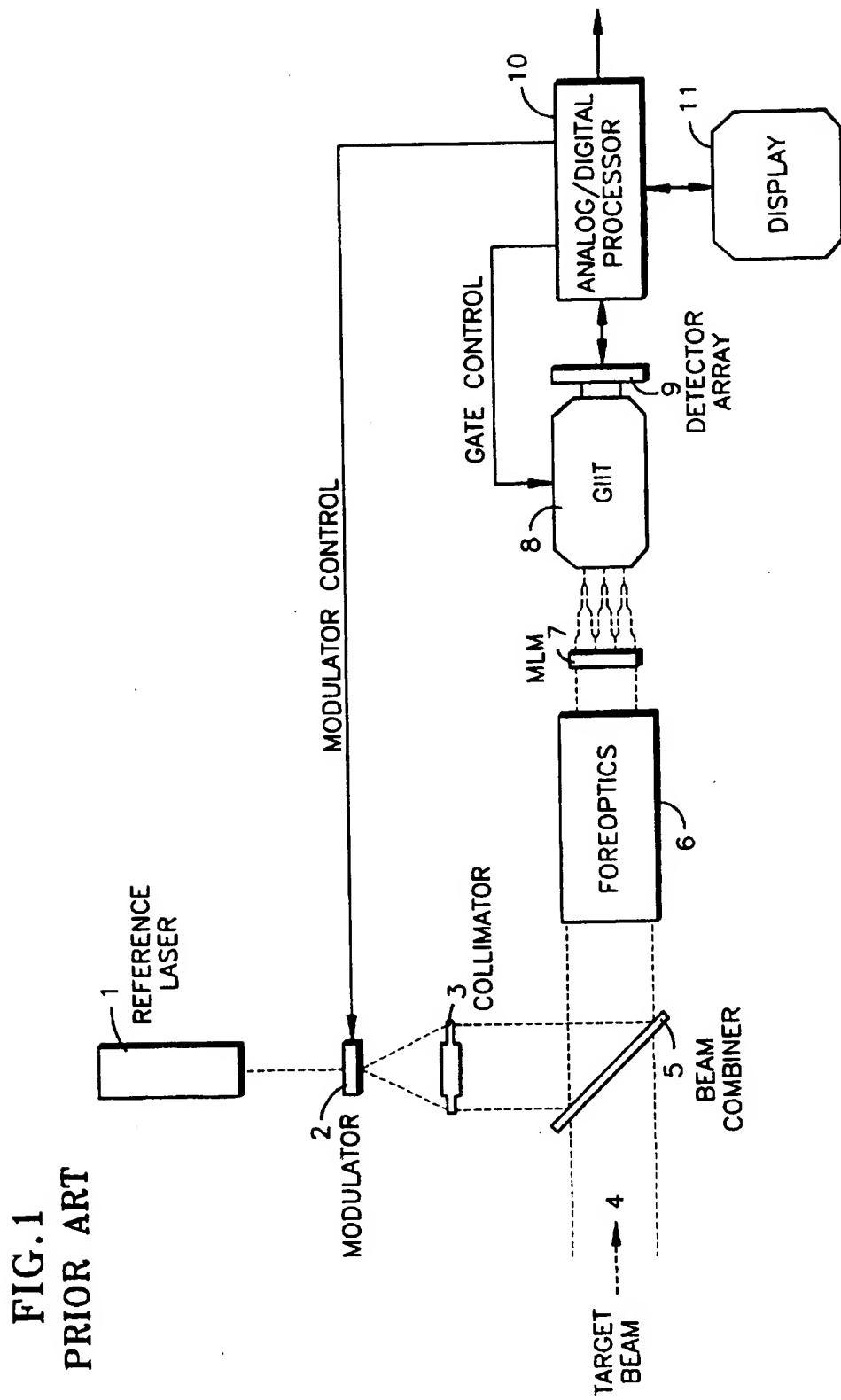
5 detector means, adapted to be mounted coaxial with said optic axis and relatively spaced at said lens focal length distance from said relay lens; and

platform means, adapted for reciprocal movement along said subaperture beam path, and adapted to receive said relay lens and said detector means in combination, in a mounting relationship which positions said optical axis substantially parallel to said subaperture beam path, said platform means being movable along said subaperture beam path to position said relay lens at said lens object distance from said MLM focal plane and, alternately, from said MLM pupil plane, to cause said relay lens to relay said subaperture spot pattern images and, alternately, said IGR spot pattern images to said detector means, said detector means alternately providing electrical signal equivalents of each type of said spot pattern images to said signal processor.

3. The sensor of claim 3, wherein said camera means further comprises:
positioning means, adapted to guide reciprocal movement of said platform means along said subaperture beam path, for positioning said platform means at a first stop position to locate said relay lens at said lens object distance from said MLM focal plane and, alternately, for positioning said platform means at a second stop position to locate said relay lens at said lens object distance from said MLM pupil plane, each in response to operator control.

4. The sensor of claim 3, wherein said first stop position is for calibrating said sensor.

1/6



2/6

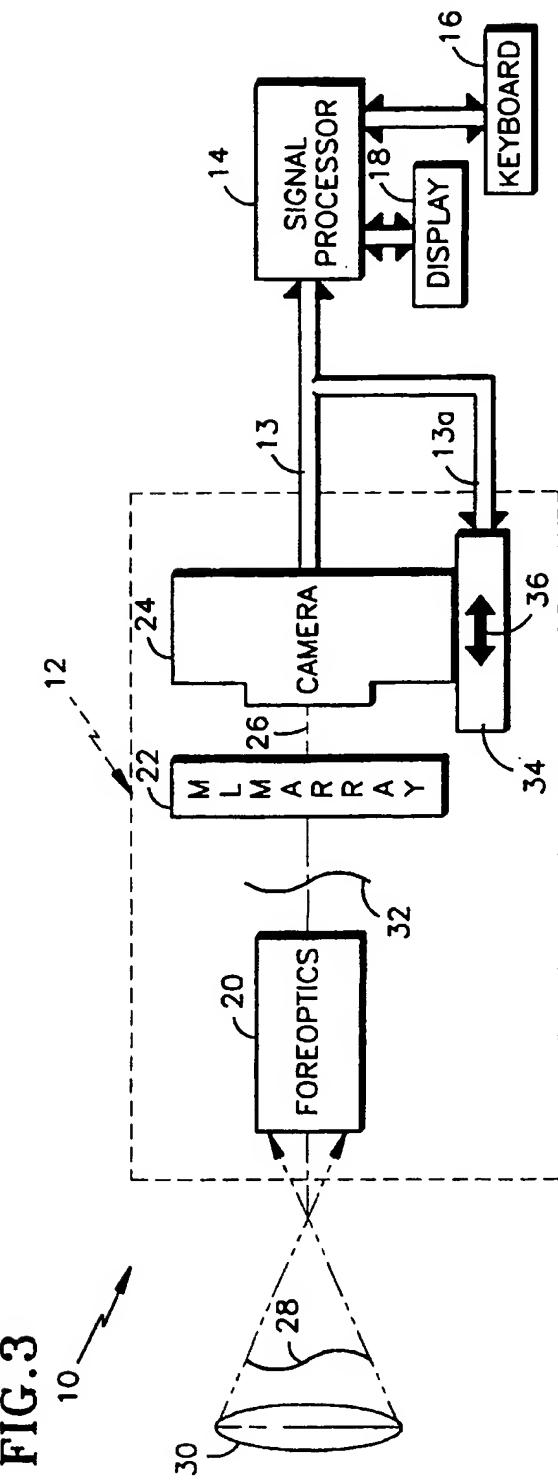
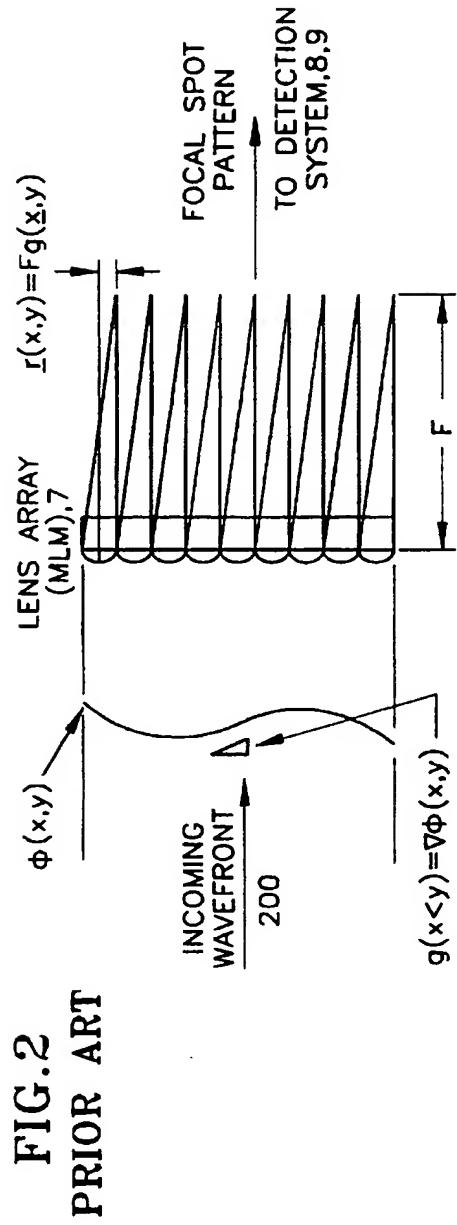
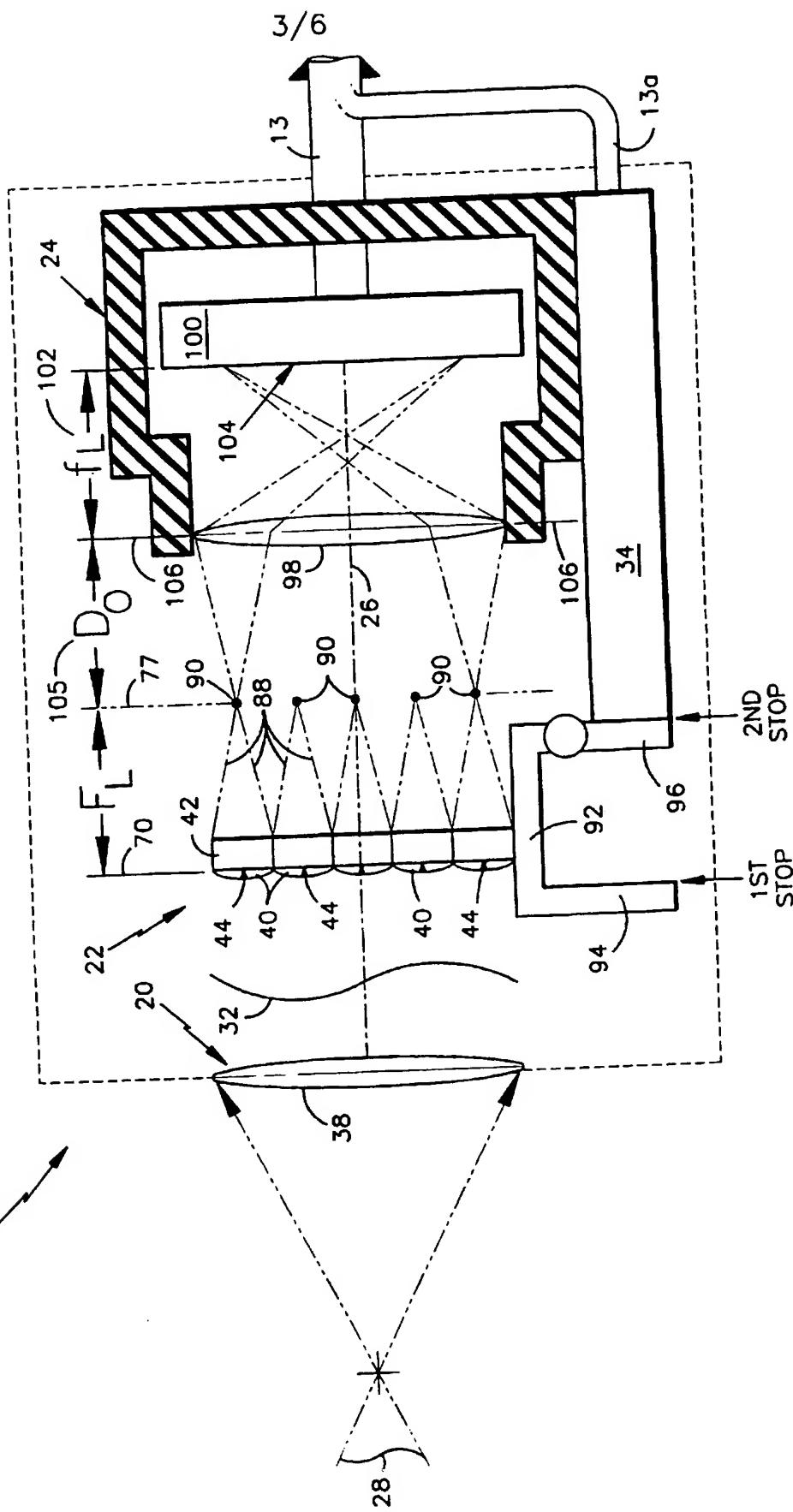


FIG. 4



4/6

FIG.5

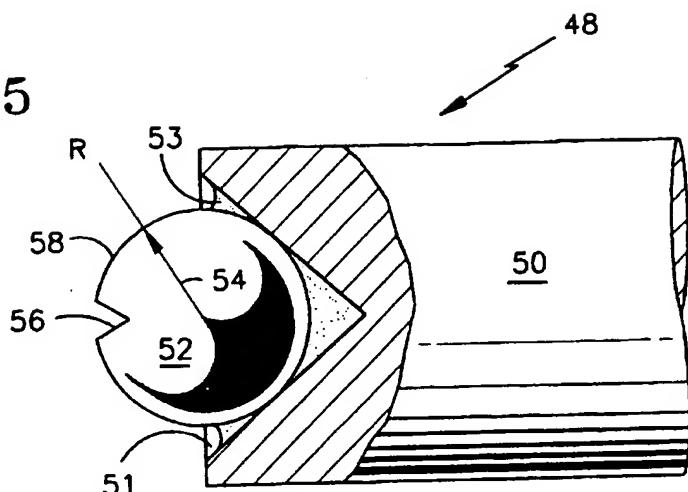
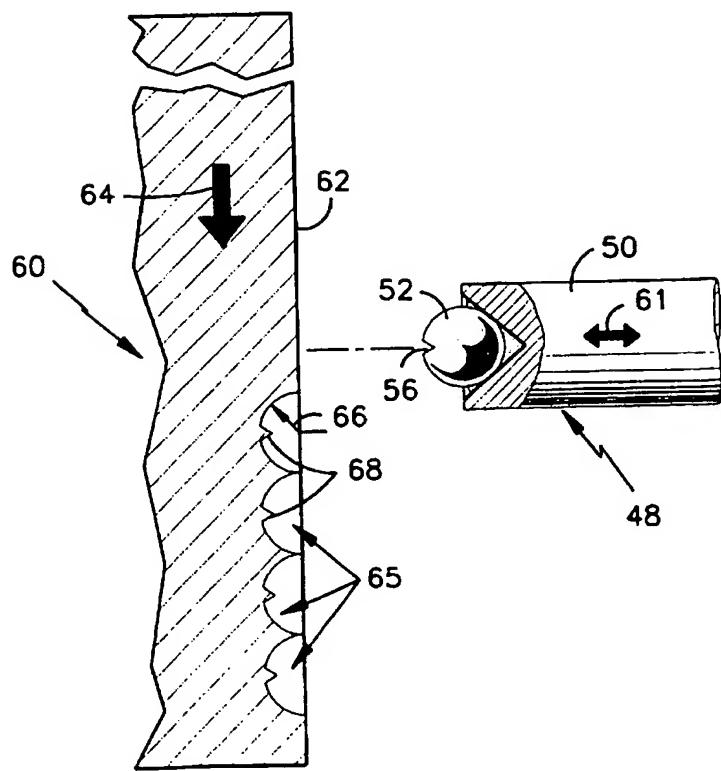


FIG. 6



5/6

FIG. 7

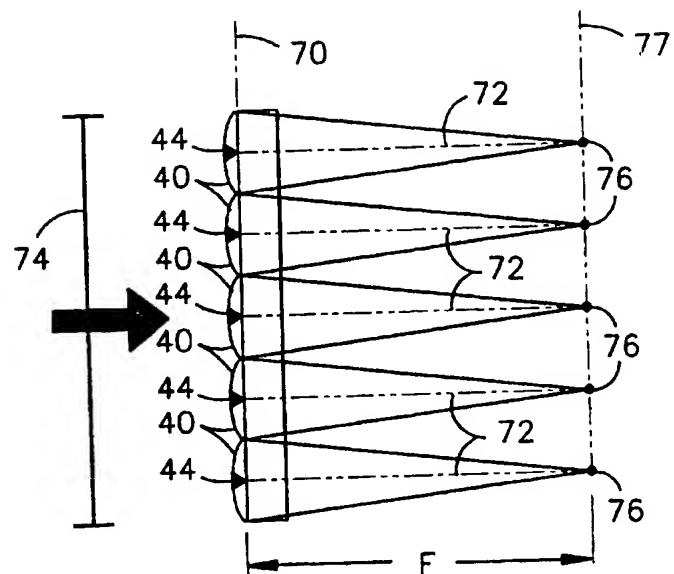
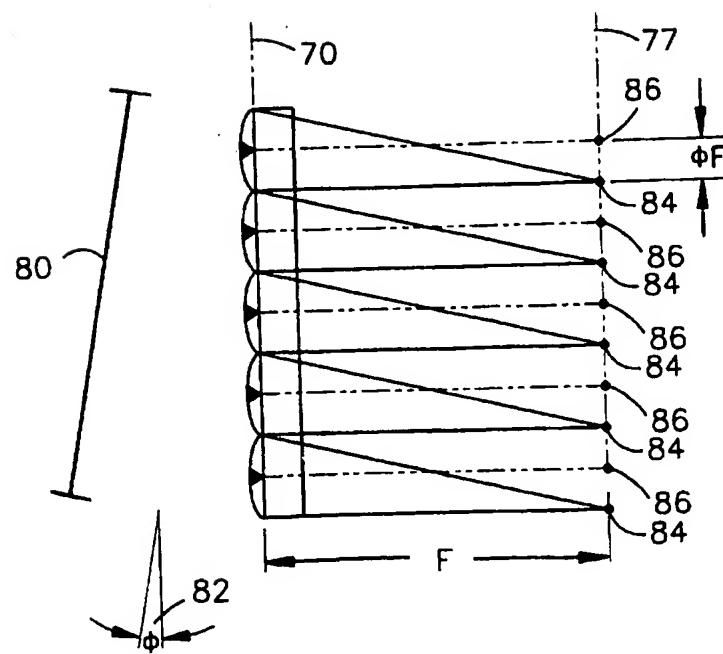
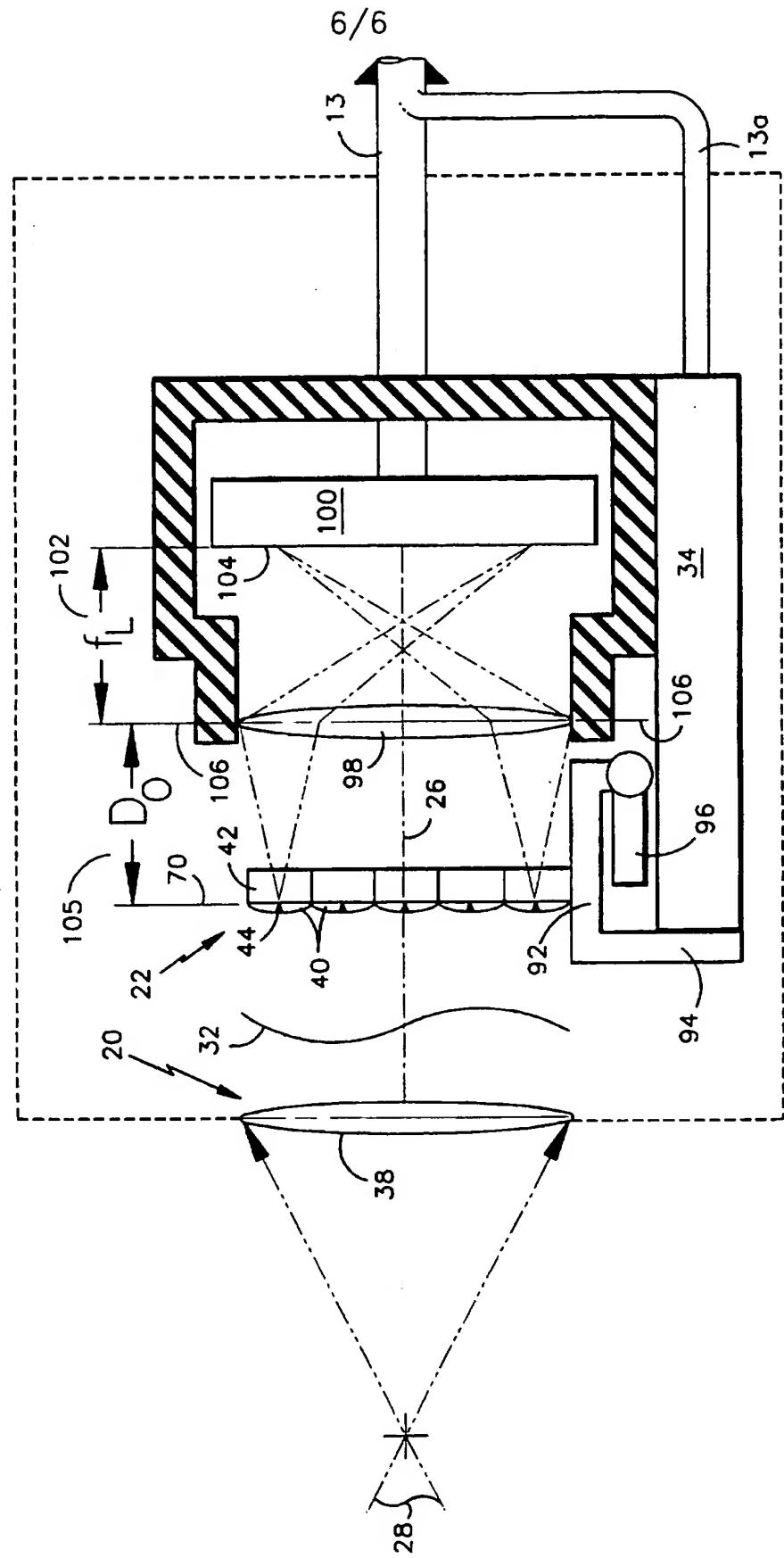


FIG. 8





INTERNATIONAL SEARCH REPORT

Internal Application No
PCT/US 96/20388

A. CLASSIFICATION OF SUBJECT MATTER
IPC 6 G01J9/00

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
IPC 6 G01J G02B

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	US H615 H (FEINLEIB JULIUS M) 4 April 1989 cited in the application see the whole document ---	1-4
A	PROCEEDINGS OF THE SPIE, vol. 1920, 1993, SAN DIEGO, pages 328-336, XP000196886 BRUNO THERESA L. ET AL.: "Applying Hartmann wavefront sensing technology to precision optical testing of the Hubble Space telescope Correctors" cited in the application see page 328 - page 333, paragraph 1; figures 1-4 ---	1-4

Further documents are listed in the continuation of box C.

Patent family members are listed in annex.

* Special categories of cited documents :

- *'A' document defining the general state of the art which is not considered to be of particular relevance
- *'E' earlier document but published on or after the international filing date
- *'L' document which may throw doubt on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)
- *'O' document referring to an oral disclosure, use, exhibition or other means
- *'P' document published prior to the international filing date but later than the priority date claimed

*'T' later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

*'X' document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

*'Y' document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art.

*'&' document member of the same patent family

1

Date of the actual completion of the international search

Date of mailing of the international search report

25.04.97

15 April 1997

Authorized officer

Navas Montero, E

Name and mailing address of the ISA
European Patent Office, P.B. 5818 Patentlaan 2
NL - 2280 HV Rijswijk
Tel. (+ 31-70) 340-2040, Tx. 31 651 epo nl.
Fax (+ 31-70) 340-3016

INTERNATIONAL SEARCH REPORT

Intern'l Application No

PCT/US 96/20388

C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	OPTICAL SPACE COMMUNICATION ECO2, PARIS, 24 - 26 APRIL 1989, vol. 1131, 24 April 1989, OTRIO G, pages 160-167, XP000089631 MICHAU V ET AL: "HARTMANN-SHACK WAVEFRONT SENSOR FOR LASER DIODE TESTING" see paragraph 1 - paragraph 5; figures 1-3 ---	1,2
A	FR 2 665 955 A (ONERA (FR)) 21 February 1992 see page 10, line 1 - line 12 see page 10, line 24 - page 11, line 8; figures 1-4 -----	1,2

1

INTERNATIONAL SEARCH REPORT

Information on patent family members

International Application No
PCT/US 96/20388

Patent document cited in search report	Publication date	Patent family member(s)	Publication date
US H615 H	04-04-89	NONE	
FR 2665955 A	21-02-92	NONE	